

*Fig. 7* Figs. 7(a) and 7(b) are other graphs showing changes in edge width against focus.

Rewrite the paragraph at page 9, line 22, as follows:

Figs. 9(a) and 9(b) are diagrams showing the acquisition of the creation sequences for the models which establish logical linking between exposure conditions and dimensional characteristic quantities.

Rewrite the paragraphs at page 10, line 4 through line 8, as follows:

*Fig. 12* Figs. 12(a) and 12(b) are diagrams of the process conditions change monitoring system pertaining to the third preferred mode of embodiment.

Figs. 13(a) and 13(b) are diagrams showing a second example of patterns suitable for process conditions change monitoring.

Rewrite the paragraphs at page 10, line 12 through line 16, as follows:

Figs. 15(a) and 15(b) are diagrams showing a third example of patterns suitable for process conditions change monitoring.

Figs. 16(a) and 16(b) are diagrams showing the measuring method in the third example of patterns suitable for process conditions change monitoring.

Rewrite the paragraphs at page 10, line 22 through line 26, as follows:

Figs. 19 a and 19 b are epitomic diagrams representing the relationship between the cross-sectional shape of a resist pattern and the level of a secondary electron signal.

Figs. 20 a and 20 b are graphs showing the relationship between exposure level, focus, and line width.